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G06-F03C; G06-F03D; L04-C05
Manual Codes (EPI/S-X): U11-A06
Polymer Indexing (PS):

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001 018; P0226 P0282-R D01 D18 F30; S9999 S1627 S1605; M9999 M2095-R;
L9999 L2391; L9999 L2095-R; K9790-R; K9847-R K9790
002 018; ND01; ND07; Q9999 Q8684 Q8673 Q8606; Q9999 Q6791; B9999 B5094
B4977 B4740; B9999 B5652 B3521 B3510 B3372; N9999 N6837 N6655;
K9585 K9483; K9610 K9483; Q9999 Q7476 Q7330; B9999 B4386 B4240
003 018; R01066 G2335 D00 F20 C- 4A O- 6A; A999 A475; K9665; K9905;
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004 018; D01 D11 D10 D50 D63 D85 F27 F26 F89 F41; A999 A475
005 018; D01 D11 D10 D50 D63 D87 F34 F89 F41; A999 A475
006 018; D01 D19 D18 D33 D76 D50 D61-R D93 B- 3A S- 6A; A999 A204
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008 018; D01 D11 D10 D19 D18 D31 D76 D50 D63 D89 F89 F41 F75; A999 A204
009 018; D01 D11 D10 D19 D18 D50 D94 F33 F30; A999 A793
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Rinsing method for photoresist - freezing rinsing liq. by applying
liquefied carbon dioxide gas and then removing rinse liquid exposing
resist

Patent Assignee: KAWASAKI STEEL CORP (KAWI)

Number of Countries: 001 Number of Patents: 001

Patent Family:

Patent No	Kind	Date	Applicat No	Kind	Date	Main IPC	Week
JP 7142333	/A	19950602	JP 93158928	A	19930629	H01L-021/027	199531 B

Priority Applications (No Kind Date): JP 93158928 A 19930629

Patent Details:

Patent	Kind	Lan	Pg	Filing Notes	Application	Patent
JP 7142333	A		7			

Abstract (Basic): JP 7142333 A

The rinsing method involves flushing of development liquid which formed a resist (3) exposed by a predetermined pattern with rinsing liquid . Liquefied carbon dioxide (6) and applied over the rinsing liquid on the resist formed over a substrate (1) separated by a thin film (2). The liquefied carbon dioxide is cooled and freezes the rinsing liquid which is then removed by exposing the resist.

ADVANTAGE - Prevents collapsing of resists pillars which have high aspect ratio withstanding effect of surface tensile force.

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Title Terms: RINSE; METHOD; PHOTORESIST ; FREEZE; RINSE; LIQUID; APPLY;
LIQUEFY; CARBON; DI; OXIDE; GAS; REMOVE; RINSE; LIQUID; EXPOSE; RESIST